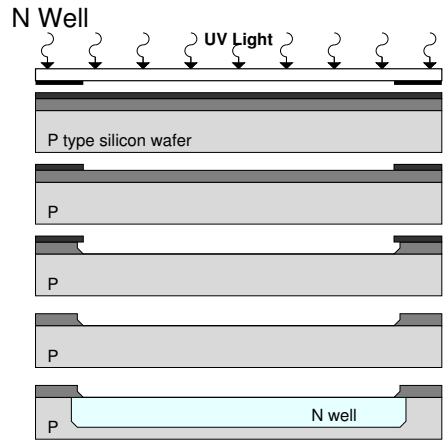
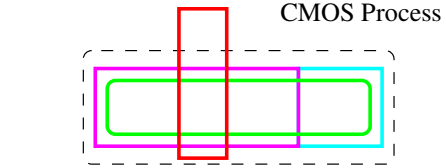


PMOS Enhancement transistor
CMOS Process



many steps for a single mask

Active Area



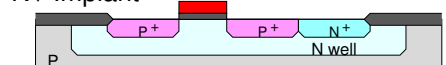
Polysilicon



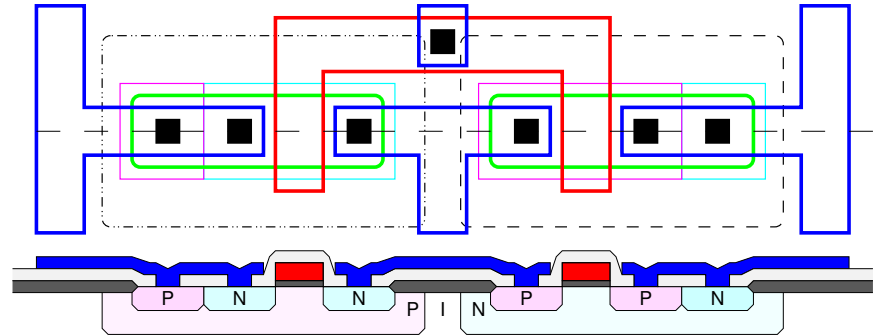
P+ Implant



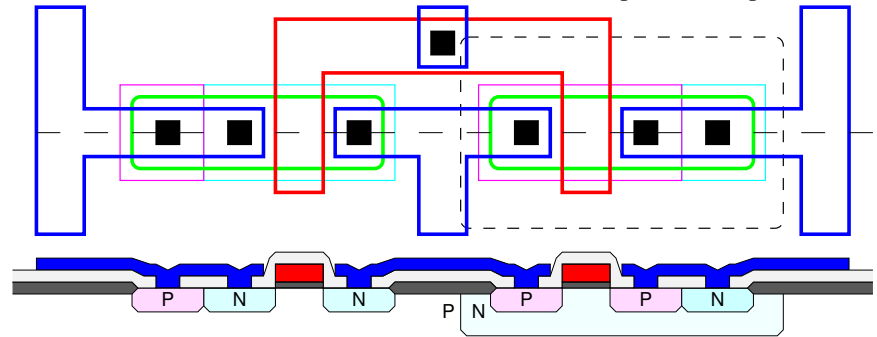
N+ Implant



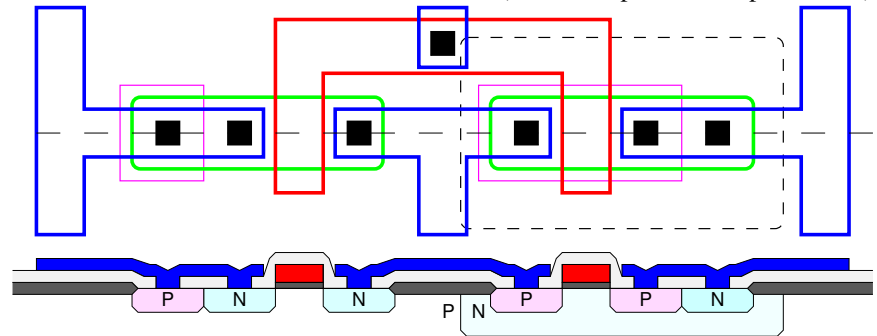
CMOS Inverter Twin Tub CMOS Process



CMOS Inverter N-Well CMOS Process (with explicit N+ implant mask)



CMOS Inverter N-Well CMOS Process (without explicit N+ implant mask)



Features may be determined by a number of masks
e.g. NMOS source drain: ActiveArea AND NOT(NWell OR Poly OR PImplant)